

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination ENGELEN ET AL.	
		Examiner John A. McPherson	Art Unit 1756	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
	D	US-			
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	G	US-			
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*	O	JP 2-173285	07-1990	Japan	Arakawa	---
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NON-PATENT DOCUMENTS

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*	U	Allen R. et al: "Deep U.V. Hardening or Positive Photoresist Patterns" Journal of the Electrochemical Society, vol. 29, no. 6, June 1982, pp. 1379-1381, XP002047660 see pages 1379-1380.
*	V	Hiraoka & Pacansky: "UV-hardening of Resist Patterns" IBM Technical Disclosure Bulletin, vol. 24, no. 3, August 1981, page 1468 XP002067935 see page 1468.
*	W	"Photoresist Stabilization System" Solid State Technology, vol. 27, no. 7, June 1984, pages 45-45, XP002067936 Washington, New York, USA see pages 45-46.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

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